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In the claims:

- 1. (original) A polymerization process comprising contacting one or more monomer(s), one or more Lewis acid(s), and a diluent comprising one or more hydrofluorocarbon(s) (HFC's) in a reactor; wherein the one or more Lewis acid(s) is not a compound represented by formula MX₃, where M is a group 13 metal and X is a halogen.
- 2. (original) The process of claim 1, wherein the one or more hydrofluorocarbon(s) is represented by the formula: $C_xH_yF_z$ wherein x is an integer from 1 to 40 and y and z are integers of one or more.
- 3. (original) The process of claim 2, wherein x is from 1 to 10.
- 4. (original) The process of claim 2, wherein x is from 1 to 6.
- 5. (original) The process of claim 2, wherein x is from 1 to 3.
- 6. (original) The process of claim 1, wherein the one or more hydrofluorocarbon(s) is independently selected from the group consisting of fluoromethane; difluoromethane; trifluoromethane; fluoroethane; 1,1-difluoroethane; 1,2-difluoroethane; 1,1,1-1,1,1,2-tetrafluoroethane; trifluoroethane; 1,1,2-trifluoroethane; 1,1,2,2tetrafluoroethane; 1,1,1,2,2-pentafluoroethane; 1-fluoropropane; 2-fluoropropane; 1,1difluoropropane; 1,2-difluoropropane; 1,3-difluoropropane; 2,2-difluoropropane; 1,1,1-trifluoropropane; 1,2,2-1,1,2-trifluoropropane; 1,1,3-trifluoropropane; trifluoropropane; 1,2,3-trifluoropropane; 1,1,1,2-tetrafluoropropane; 1,1,1,3tetrafluoropropane; 1,1,2,2-tetrafluoropropane; 1,1,2,3-tetrafluoropropane; 1,1,3,3tetrafluoropropane; 1,2,2,3-tetrafluoropropane; 1,1,2,2-pentafluoropropane; 1,1,1,2,3-pentafluoropropane; 1,1,1,3,3-pentafluoropropane; 1,1,2,2,3pentafluoropropane; 1,1,2,3,3-pentafluoropropane; 1,1,1,2,2,3-hexafluoropropane; 1,1,1,3,3,3-hexafluoropropane; 1,1,1,2,3,3-hexafluoropropane; 1,1,1,2,2,3,3-1-fluorobutane; heptafluoropropane; 1,1,2,3,3,3-heptafluoropropane; 2fluorobutane; 1,1-difluorobutane; 1,2-difluorobutane; 1,3-difluorobutane; 1,4-

difluorobutane; 2,2-difluorobutane; 2,3-difluorobutane; 1,1,1-trifluorobutane; 1,1,2trifluorobutane; 1,1,3-trifluorobutane; 1,1,4-trifluorobutane; 1,2,2-trifluorobutane; 1,2,3-trifluorobutane; 1,3,3-trifluorobutane; 2,2,3-trifluorobutane; 1,1,1,2tetrafluorobutane; 1,1,3-tetrafluorobutane; 1,1,4-tetrafluorobutane; 1,1,2,2-1,1,2,4-tetrafluorobutane; tetrafluorobutane; 1,1,2,3-tetrafluorobutane; 1,1,3,3-1,1,3,4-tetrafluorobutane; 1,1,4,4-tetrafluorobutane; tetrafluorobutane; 1,2,2,3tetrafluorobutane; 1,2,2,4-tetrafluorobutane; 1,2,3,3-tetrafluorobutane; 1,2,3,4tetrafluorobutane; 2,2,3,3-tetrafluorobutane; 1,1,1,2,2-pentafluorobutane; 1,1,1,2,3pentafluorobutane; 1,1,1,2,4-pentafluorobutane; 1,1,1,3,3-pentafluorobutane; 1,1,1,4,4-pentafluorobutane; 1,1,1,3,4-pentafluorobutane; 1,1,2,2,3pentafluorobutane; 1,1,2,2,4-pentafluorobutane; 1,1,2,3,3-pentafluorobutane; 1,1,2,4,4-pentafluorobutane; 1,1,3,3,4-pentafluorobutane; 1,2,2,3,3-1,2,2,3,4-pentafluorobutane; 1,1,1,2,2,3-hexafluorobutane; pentafluorobutane; 1,1,1,2,2,4-hexafluorobutane; 1,1,1,2,3,3-hexafluorobutane, 1,1,1,2,3,4hexafluorobutane; 1,1,1,2,4,4-hexafluorobutane; 1,1,1,3,3,4-hexafluorobutane; 1,1,1,3,4,4-hexafluorobutane; 1,1,1,4,4,4-hexafluorobutane; 1,1,2,2,3,3hexafluorobutane; 1,1,2,2,3,4-hexafluorobutane; 1,1,2,2,4,4-hexafluorobutane; 1,1,2,3,3,4-hexafluorobutane; 1,1,2,3,4,4-hexafluorobutane; 1,2,2,3,3,4hexafluorobutane; 1,1,1,2,2,3,3-heptafluorobutane; 1,1,1,2,2,4,4-heptafluorobutane; 1,1,1,2,2,3,4-heptafluorobutane; 1,1,1,2,3,3,4-heptafluorobutane; 1,1,1,2,3,4,4heptafluorobutane; 1,1,1,2,4,4,4-heptafluorobutane; 1,1,1,3,3,4,4-heptafluorobutane; 1,1,1,2,2,3,3,4-octafluorobutane; 1,1,1,2,2,3,4,4-octafluorobutane; 1,1,1,2,3,3,4,4octafluorobutane; 1,1,1,2,2,4,4,4-octafluorobutane; 1,1,1,2,3,4,4,4-octafluorobutane; 1,1,1,2,2,3,3,4,4-nonafluorobutane; 1,1,1,2,2,3,4,4,4-nonafluorobutane; 1-fluoro-2methylpropane; 1,1-difluoro-2-methylpropane; 1,3-difluoro-2-methylpropane; 1,1,1trifluoro-2-methylpropane; 1,1,3-trifluoro-2-methylpropane; 1,3-difluoro-2-(fluoromethyl)propane; 1,1,1,3-tetrafluoro-2-methylpropane; 1,1,3,3-tetrafluoro-2methylpropane; 1,1,3-trifluoro-2-(fluoromethyl)propane; 1,1,1,3,3-pentafluoro-2methylpropane; 1,1,3,3-tetrafluoro-2-(fluoromethyl)propane; 1,1,1,3-tetrafluoro-2fluorocyclobutane; 1,1-difluorocyclobutane; 1,2-(fluoromethyl)propane; difluorocyclobutane; 1,3-difluorocyclobutane; 1,1,2-trifluorocyclobutane; 1,1,3-1,1,2,2-tetrafluorocyclobutane; trifluorocyclobutane; 1,2,3-trifluorocyclobutane; 1,1,3,3-tetrafluorocyclobutane; 1,1,2,2,3-pentafluorocyclobutane; 1,1,2,3,3pentafluorocyclobutane; 1,1,2,2,3,3-hexafluorocyclobutane; 1,1,2,2,3,4-1,1,2,3,3,4-hexafluorocyclobutane; 1,1,2,2,3,3,4hexafluorocyclobutane; heptafluorocyclobutane; vinyl fluoride; 1,1-difluoroethene; 1,2-difluoroethene; 1,1,2trifluoroethene; 1-fluoropropene, 1,1-difluoropropene; 1,2-difluoropropene; 1,3difluoropropene; 2,3-difluoropropene; 3,3-difluoropropene; 1,1,2-trifluoropropene; 1,2,3-trifluoropropene; 1,3,3-trifluoropropene; 1,1,3-trifluoropropene; 2,3,3trifluoropropene; 3,3,3-trifluoropropene; 1-fluoro-1-butene; 2-fluoro-1-butene; 3fluoro-1-butene; 4-fluoro-1-butene; 1,1-difluoro-1-butene; 1,2-difluoro-1-butene; 1,3difluoropropene; 1,4-difluoro-1-butene; 2,3-difluoro-1-butene; 2,4-difluoro-1-butene; 3,3-difluoro-1-butene; 3,4-difluoro-1-butene; 1,1,2-trifluoro-1butene; 1,1,3-trifluoro-1-butene; 1,1,4-trifluoro-1-butene; 1,2,3-trifluoro-1-butene; 1,2,4-trifluoro-1-butene; 1,3,3-trifluoro-1-butene; 1,3,4-trifluoro-1-butene; 1,4,4trifluoro-1-butene; 2,3,3-trifluoro-1-butene; 2,3,4-trifluoro-1-butene; 2,4,4-trifluoro-1butene; 3,3,4-trifluoro-1-butene; 4,4,4-trifluoro-1-butene; 1,1,2,3-tetrafluoro-1-butene; 1,1,2,4-tetrafluoro-1-butene; 1,1,3,3-tetrafluoro-1butene; 1,1,3,4-tetrafluoro-1-butene; 1,1,4,4-tetrafluoro-1-butene; 1,2,3,3-tetrafluoro-1-butene: 1,2,3,4-tetrafluoro-1-butene; 1,2,4,4-tetrafluoro-1-butene; 1,3,3,4tetrafluoro-1-butene; 1,3,4,4-tetrafluoro-1-butene; 1,4,4,4-tetrafluoro-1-butene; 2,3,3,4-tetrafluoro-1-butene; 2,3,4,4-tetrafluoro-1-butene; 2,4,4,4-tetrafluoro-1butene; 3,3,4,4-tetrafluoro-1-butene; 3,4,4,4-tetrafluoro-1-butene; 1,1,2,3,3pentafluoro-1-butene; 1,1,2,3,4-pentafluoro-1-butene; 1,1,2,4,4-pentafluoro-1-butene; 1,1,3,3,4-pentafluoro-1-butene; 1,1,3,4,4-pentafluoro-1-butene; 1,1,4,4,4-pentafluoro-1-butene; 1,2,3,3,4-pentafluoro-1-butene; 1,2,3,4,4-pentafluoro-1-butene; 1,2,4,4,4pentafluoro-1-butene; 2,3,3,4,4-pentafluoro-1-butene; 2,3,4,4,4-pentafluoro-1-butene; 1,1,2,3,3,4-hexafluoro-1-butene; 3,3,4,4,4-pentafluoro-1-butene; 1,1,2,3,4,4hexafluoro-1-butene; 1,1,2,4,4,4-hexafluoro-1-butene; 1,2,3,3,4,4-hexafluoro-1butene; 1,2,3,4,4,4-hexafluoro-1-butene; 2,3,3,4,4,4-hexafluoro-1-butene; 1,1,2,3,3,4,4-heptafluoro-1-butene; 1,1,2,3,4,4,4-heptafluoro-1-butene; 1,1,3,3,4,4,4heptafluoro-1-butene; 1,2,3,3,4,4,4-heptafluoro-1-butene; 1-fluoro-2-butene; 2-fluoro-2-butene; 1,1-difluoro-2-butene; 1,2-difluoro-2-butene; 1,4difluoro-2-butene; 2,3-difluro-2-butene; 1,1,1-trifluoro-2-butene; 1,1,2-trifluoro-2butene; 1,1,3-trifluoro-2-butene; 1,1,4-trifluoro-2-butene; 1,2,3-trifluoro-2-butene; 1,2,4-trifluoro-2-butene; 1,1,1,2-tetrafluoro-2-butene; 1,1,1,3-tetrafluoro-2-butene;

1,1,2,3-tetrafluoro-2-butene; 1,1,2,4-tetrafluoro-2-1,1,4-tetrafluoro-2-butene; 1,2,3,4-tetrafluoro-2-butene; 1,1,1,2,3-pentafluoro-2-butene; 1,1,1,2,4butene; pentafluoro-2-butene; 1,1,1,3,4-pentafluoro-2-butene; 1,1,1,4,4-pentafluoro-2-butene; 1,1,2,3,4-pentafluoro-2-butene; 1,1,2,4,4-pentafluoro-2-butene; 1,1,1,2,3,4hexafluoro-2-butene; 1,1,1,2,4,4-hexafluoro-2-butene; 1,1,1,3,4,4-hexafluoro-2-1,1,2,3,4,4-hexafluoro-2-butene; 1,1,1,4,4,4-hexafluoro-2-butene; butene: 1,1,1,2,3,4,4-heptafluoro-2-butene; 1,1,1,2,4,4,4-heptafluoro-2-butene; and mixtures thereof.

- 7. (original) The process of claim 1, wherein the one or more hydrofluorocarbon(s) is independently selected from the group consisting of fluoromethane, difluoromethane, trifluoromethane, 1,1-difluoroethane, 1,1,1-trifluoroethane, 1,1,1,2-tetrafluoroethane, and mixtures thereof.
- 8. (currently amended) The process of any of claims 1 to 7 claim 1, wherein the diluent comprises from 15 to 100 volume % HFC based upon the total volume of the diluent.
- 9. (original) The process of claim 8, wherein the diluent comprises from 20 to 100 volume % HFC based upon the total volume of the diluent.
- 10. (original) The process of claim 9, wherein the diluent comprises from 25 to 100 volume % HFC based upon the total volume of the diluent.
- 11. (currently amended) The process of any of claims 1 to 10 claim 1, wherein the diluent further comprises a hydrocarbon, a non-reactive olefin, and/or an inert gas.
- 12. (original) The process of claim 11, wherein the hydrocarbon is a halogenated hydrocarbon other than an HFC.
- 13. (original) The process of claim 12, wherein the halogenated hydrocarbon is methyl chloride.

- 14. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula MX₄; wherein M is a Group 4, 5, or 14 metal; and each X is a halogen.
- 15. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula MR_nX_{4-n}; wherein M is Group 4, 5, or 14 metal; each R is a monovalent C₁ to C₁₂ hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals; n is an integer from 0 to 4; and each X is a halogen.
- (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula M(RO)_nR'_mX_{4-(m+n)}; wherein M is Group 4, 5, or 14 metal; each RO is a monovalent C₁ to C₃₀ hydrocarboxy radical independently selected from the group consisting of an alkoxy, aryloxy, arylalkoxy, alkylaryloxy radicals; each R' is a monovalent C₁ to C₁₂ hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals; n is an integer from 0 to 4; m is an integer from 0 to 4, wherein the sum of n and m is not more than 4; and each X is a halogen.
- 17. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula M(RC=OO)_nR'_mX_{4-(m+n)}; wherein M is Group 4, 5, or 14 metal; each RC=OO is a monovalent C₂ to C₃₀ hydrocarbacyl radical independently selected from the group consisting of an alkacyloxy, arylacyloxy, arylacyloxy radicals; each R' is a monovalent C₁ to C₁₂ hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals; n is an integer from 0 to 4;

m is an integer from 0 to 4, wherein the sum of n and m is not more than 4; and each X is a halogen.

- 18. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula MOX₃; wherein M is a Group 5 metal; and each X is a halogen.
- 19. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula MR_nX_{3-n}; wherein M is a Group 13 metal; each R is a monovalent C₁ to C₁₂ hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals; n is an integer from 1 to 3; and each X is a halogen.
- 20. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula M(RO)_nR'_mX_{3-(m+n)}; wherein M is a Group 13 metal; each RO is a monovalent C₁ to C₃₀ hydrocarboxy radical independently selected from the group consisting of an alkoxy, aryloxy, arylalkoxy, alkylaryloxy radicals; each R' is a monovalent C₁ to C₁₂ hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals; n is an integer from 0 to 3; m is an integer from 0 to 3, wherein the sum of n and m is from 1 to 3; and each X is a halogen.
- 21. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula M(RC=OO)_nR'_mX_{3-(m+n)}; wherein M is a Group 13 metal; each RC=OO is a monovalent C₂ to C₃₀ hydrocarbacyl radical independently selected from the group independently selected from the group consisting of an alkacyloxy, arylacyloxy, arylalkylacyloxy, alkylarylacyloxy radicals;

each R' is a monovalent C_1 to C_{12} hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals; n is an integer from 0 to 3; m is a integer from 0 to 3, wherein the sum of n and m is from 1 to 3; and each X is a halogen.

22. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula MX_y; wherein M is a Group 15 metal; each X is a halogen; and y is 3, 4 or 5.

23. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula MR_nX_{y-n}; wherein M is a Group 15 metal; each R is a monovalent C₁ to C₁₂ hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals; n is an integer from 0 to 4; y is 3, 4 or 5, wherein n is less than y; and each X is a halogen.

24. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula M(RO)_nR'_mX_{y-(m+n)}; wherein M is a Group 15 metal, each RO is a monovalent C₁ to C₃₀ hydrocarboxy radical independently selected from the group consisting of an alkoxy, aryloxy, arylalkoxy, alkylaryloxy radicals; each R' is a monovalent C₁ to C₁₂ hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals; n is an integer from 0 to 4; m is an integer from 0 to 4; y is 3, 4 or 5, wherein the sum of n and m is less than y; and each X is a halogen.

25. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is represented by the formula M(RC=OO)_nR'_mX_{y-(m+n)}; wherein M is a Group 15 metal;

each RC=OO is a monovalent C_2 to C_{30} hydrocarbacyloxy radical independently selected from the group consisting of an alkacyloxy, arylacyloxy, arylacyloxy radicals;

each R' is a monovalent C_1 to C_{12} hydrocarbon radical independently selected from the group consisting of an alkyl, aryl, arylalkyl, alkylaryl and cycloalkyl radicals;

n is an integer from 0 to 4;m is an integer from 0 to 4;

y is 3, 4 or 5, wherein the sum of n and m is less than y; and each X is a halogen.

26. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is independently selected from the group consisting of titanium tetrachloride, titanium tetrabromide, vanadium tetrachloride, tin tetrachloride, zirconium tetrachloride, titanium bromide trichloride, titanium dibromide dichloride, vanadium bromide trichloride, tin chloride trifluoride, benzyltitanium trichloride, dibenzyltitanium dichloride, benzylzirconium trichloride, dibenzylzirconium dibromide, methyltitanium trichloride, dimethyltitanium difluoride, dimethyltin dichloride. phenylvanadium trichloride, methoxytitanium trichloride. butoxytitanium trichloride, di(isopropoxy)titanium dichloride, phenoxytitanium tribromide, phenylmethoxyzirconium trifluoride, methyl methoxytitanium dichloride, methoxytin dichloride, benzyl isopropoxyvanadium methyl dichloride, acetoxytitanium trichloride, benzoylzirconium tribromide, benzoyloxytitanium trifluoride, isopropoyloxytin trichloride, methyl acetoxytitanium dichloride, benzyl benzoyloxyvanadium chloride, vanadium oxytrichloride, ethylaluminum dichloride, methylaluminum dichloride, benzylaluminum dichloride, isobutylgallium dichloride, diethylaluminum chloride, dimethylaluminum chloride, ethylaluminum sesquichloride, methylaluminum sesquichloride trimethylaluminum, triethylaluminum, methoxyaluminum dichloride, ethoxyaluminum dichloride, 2,6-ditert-butylphenoxyaluminum dichloride, methoxy methylaluminum chloride, 2,6-ditert-butylphenoxy methylaluminum chloride, isopropoxygallium dichloride, phenoxy

methylindium fluoride, acetoxyaluminum dichloride, benzoyloxyaluminum dibromide, benzoyloxygallium difluoride, methyl acetoxyaluminum chloride, isopropoyloxyindium trichloride, antimony hexachloride, antimony hexafluoride, arsenic pentafluoride, antimony chloride pentafluoride, arsenic trifluoride, bismuth fluoride tetrachloride, trichloride arsenic tetraphenylantimony chloride, triphenylantimony dichloride, tetrachloromethoxyantimony, dimethoxytrichloroantimony, dichloromethoxyarsine, chlorodimethoxyarsine, difluoromethoxyarsine, acetatotetrachloroantimony, (benzoato) tetrachloroantimony, and bismuth acetate chloride.

- 27. (currently amended) The process of any of claims 1 to 13 claim 1, wherein the one or more Lewis acid(s) is independently selected from the group consisting of ethylaluminum dichloride, ethylaluminum sesquichloride, diethylaluminum chloride, methylaluminum sesquichloride, dimethylaluminum chloride, and titanium tetrachloride.
- 28. (currently amended) The process of any of claims 1 to 27 claim 1, wherein the process further comprises one or more initiator(s) is independently selected from the group consisting of a hydrogen halide, a carboxylic acid, a carboxylic acid halide, a sulfonic acid, an alcohol, a phenol, a polymeric halide, a tertiary alkyl halide, a tertiary aralkyl halide, a tertiary alkyl ester, a tertiary aralkyl ester, a tertiary alkyl ether, a tertiary aralkyl ether, an alkyl halide, an aryl halide, an alkylaryl halide and an arylalkylacid halide.
- 29. (currently amended) The process of any of claims 1 to 27 claim 1, wherein the process further comprises one or more initiator(s) is independently selected from the group consisting of HCl, H₂O, methanol, (CH₃)₃CCl, C₆H₅C(CH₃)₂Cl, (2-Chloro-2,4,4-trimethylpentane) and 2-chloro-2-methylpropane.
- 30. (currently amended) The process of any of claims 1 to 27 claim 1, wherein the process further comprises one or more initiator(s) is independently selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen iodide, acetic acid, propanoic acid, butanoic acid; cinnamic acid, benzoic acid, 1-chloroacetic acid,

dichloroacetic acid, trichloroacetic acid, trifluoroacetic acid, p-chlorobenzoic acid, pfluorobenzoic acid, acetyl chloride, acetyl bromide, cinnamyl chloride, benzoyl chloride, benzoyl bromide, trichloroacetylchloride, trifluoroacetylchloride, pfluorobenzoylchloride, methanesulfonic acid, trifluoromethanesulfonic acid. trichloromethanesulfonic acid, p-toluenesulfonic acid, methanesulfonyl chloride, trichloromethanesulfonyl methanesulfonyl bromide, chloride. trifluoromethanesulfonyl chloride, p-toluenesulfonyl chloride, methanol, ethanol, propanol, 2-propanol, 2-methylpropan-2-ol, cyclohexanol, benzyl alcohol, phenol, 2methylphenol, 2,6-dimethylphenol, p-chlorophenol, p-fluorophenol, 2,3,4,5,6pentafluorophenol, and 2-hydroxynaphthalene.

- 31. (currently amended) The process of any of claims 1 to 27 claim 1, wherein the process further comprises one or more initiator(s) is independently selected from the group consisting of 2-chloro-2,4,4-trimethylpentane; 2-bromo-2,4,4-trimethylpentane; 2-chloro-2-methylpropane; 2-bromo-2-methylpropane; 2-chloro-2,4,4,6,6pentamethylheptane; 2-bromo-2,4,4,6,6-pentamethylheptane; 1-chloro-1methylethylbenzene; 1-chloroadamantane; 1-chloroethylbenzene; 1, 4-bis(1-chloro-1methylethyl) benzene; 5-tert-butyl-1,3-bis(1-chloro-1-methylethyl) benzene; 2acetoxy-2,4,4-trimethylpentane; 2-benzoyloxy-2,4,4-trimethylpentane; 2-acetoxy-2methylpropane; 2-benzoyloxy-2-methylpropane; 2-acetoxy-2,4,4,6,6-2-benzoyl-2,4,4,6,6-pentamethylheptane; 1-acetoxy-1pentamethylheptane; methylethylbenzene; 1-aceotxyadamantane; 1-benzoyloxyethylbenzene; 1,4-bis(1acetoxy-1-methylethyl) benzene; 5-tert-butyl-1,3-bis(1-acetoxy-1-methylethyl) benzene; 2-methoxy-2,4,4-trimethylpentane; 2-isopropoxy-2,4,4-trimethylpentane; 2methoxy-2-methylpropane; 2-benzyloxy-2-methylpropane; 2-methoxy-2,4,4,6,6-2-isopropoxy-2,4,4,6,6-pentamethylheptane; pentamethylheptane; 1-methoxy-1-1-methoxyadamantane; 1-methoxyethylbenzene; 1,4-bis(1methylethylbenzene; methoxy-1-methylethyl) benzene; 5-tert-butyl-1,3-bis(1-methoxy-1-methylethyl) benzene, and 1,3,5-tris(1-chloro-1-methylethyl) benzene.
- 32. (currently amended) The process of any of claims 1 to 31 claim 1, wherein the process further comprises a weakly-coordinating anion.

- 33. (currently amended) The process of any of claims 1 to 32 claim 1, wherein the process is substantially absent of water.
- 34. (currently amended) The process of any of claims 1 to 32 claim 1, wherein the process further comprises one or more initiator(s) comprise greater than 30 ppm water (based upon weight).
- 35. (currently amended) The process of any of claims 1-to 34 claim 1, wherein the one or more monomer(s) is independently selected from the group consisting of olefins, alpha-olefins, disubstituted olefins, isoolefins, conjugated dienes, non-conjugated dienes, styrenics, substituted styrenics, and vinyl ethers.
- 36. (currently amended) The process of elaim 35 claim 1, wherein the one or more monomer(s) is independently selected from the group consisting of styrene, paraalkylstyrene, para-methylstyrene, alpha-methyl styrene, divinylbenzene, diisopropenylbenzene, isobutylene, 2-methyl-1-butene, 3-methyl-1-butene, 2-methyl-2-pentene, isoprene, butadiene, 2,3-dimethyl-1,3-butadiene, β-pinene, myrcene, 6,6-dimethyl-fulvene, hexadiene, cyclopentadiene, methyl cyclopentadiene, piperylene, methyl vinyl ether, ethyl vinyl ether, and isobutyl vinyl ether.
- 37. (currently amended) The process of any of claims 1 to 36 claim 1, wherein the reactor is independently selected from the group consisting of a continuous flow stirred tank reactor, a plug flow reactor, a moving belt or drum reactor, a jet or nozzle reactor, a tubular reactor, a batch reactor, and an autorefrigerated boiling-pool reactor.
- 38. (currently amended) The polymerization process of any of claims 1 to 37 claim 1 wherein the diluent has a dielectric constant greater than 10 at -85°C.
- 39. (original) The process of claim 38, wherein the dielectric constant is greater than 20 at -85°C.
- 40. (original) The process of claim 39, wherein the dielectric constant is greater than 25 at -85°C.

- 41. (original) The process of claim 40, wherein the dielectric constant is greater than 40 at -85°C.
- 42. (currently amended) The polymerization process of any of claims 1 to 41 to form claim 1, wherein the process forms a polymer having a diluent mass uptake of less than 4 wt%.
- 43. (original) The process of claim 42, wherein the polymer has a diluent mass uptake of less than 3 wt%.
- 44. (original) The process of claim 43, wherein the polymer has a diluent mass uptake of less than 2 wt%.
- 45. (original) The process of claim 44, wherein the polymer has a diluent mass uptake of less than 1 wt%.
- 46. (original) The process of claim 45, wherein the polymer has a diluent mass uptake of less than 0.5 wt%.
- 47. (currently amended) The polymerization process of any of claims 1, 8 to 10 or 14 to 46 claim 1, the diluent comprising methyl chloride and one or more hydrofluorocarbon(s) independently selected from the group consisting of difluoromethane, 1,1-difluoroethane, and 1,1,1,2-tetrafluoroethane in a reactor.
- 48. (original) The process of claim 47, wherein the diluent further comprises a non-reactive olefin, and/or an inert gas.
- 49. (currently amended) The polymerization process of claim 1 or any of claims 2 to 48, the process comprising the steps of: reacting the one or more monomer(s) in the presence of one or more Lewis acid(s), one or more initiator(s), and a diluent comprising one or more hydrofluorocarbon(s) (HFC's); and

withdrawing the polymer from the reactor.

- 50. (currently amended) The polymerization process of claim 1 or any of claims 2 to 48, the process comprising the steps of:
 - (a) introducing one or more monomer(s) into a reactor;
 - (b) adding one or more Lewis acid(s) and one or more initiator(s);
 - (c) introducing a diluent comprising one or more hydrofluorocarbon(s) (HFC's); and
 - (d) withdrawing a polymer from the reactor.
- 51. (currently amended) The polymerization process of claim 1 or any of claims 2 to 48 in which particles of polymer are polymerized in a slurry using a catalyst system and a diluent comprising one or more hydrofluorocarbon(s) (HFC's).
- 52. (currently amended) A composition comprising the product obtainable by the polymerization process of any of claims 1, 2 to 48, 49, 50 or 51 claim 1.
- 53. (original) A polymerization medium suitable to polymerize one or more monomer(s) to form a polymer, the polymerization medium comprising one or more Lewis acid(s) and a diluent comprising one or more hydrofluorocarbon(s) (HFC); wherein the one or more Lewis acid(s) is not a compound represented by formula MX₃, where M is a group 13 metal and X is a halogen.
- 54. (cancelled)
- 55. (currently amended) A homopolymer, copolymer, or terpolymer obtainable by the process of any of claims 1 to 48, 49, 50 and 51, or by the use of the composition of claim 52 or the polymerization medium of claim 53 or claim 54 claim 1.
- 56. (original) The homopolymer, copolymer, or terpolymer of claim 55, wherein the polymer has a Mw greater than 10,000.

57. (original) The homopolymer, copolymer, or terpolymer of claim 56, wherein the polymer has a Mw greater than 50,000.

58. (original) The homopolymer, copolymer, or terpolymer of claim 57, wherein the polymer has a Mw greater than 100,000.